INFORMATION DISCLOSURE CITATION

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Docket Number (Optional)	Application Number
SEC.74[illegible]	09/715,041
Applicant(s)	
Sang-jun Choi et al.	
Filing Date	**Group Art Unit**
11/20/00	1752

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

OIPE JC#17
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FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES	Translation NO

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OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

	A	R.D. Allen et al., "Cyclic Olefin Resist Polymers and Polymerizations for Improved Etch Resistance," Journal of Photopolymer Science and Technology, Volume 12, Number 3 (1999) pages 501-508.
	B	Koji Nozaki et al., "A Novel Polymer for a 193-nm Resist," Journal of Photopolymer Science and Technology, Volume 9, Number 3 (1996) pages 509-522.

EXAMINER	DATE CONSIDERED
Matthew M Clu	1/22/02

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Docket Number (Optional)	Application Number
SEC.741	NEW
Applicant(s)	
Sang-jun CHOI et al.	
Filing Date	**Group Art Unit**
NOV. 20, 2000	TO BE ASSIGNED

*EXAMINER INITIAL		OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*
	A	R.D. Allen et al., "Cyclic Olefin Resist Polymers and Polymerizations for Improved Etch Resistance," Journal of Photopolymer Science and Technology, Volume 12, Number 3 (1999), pages 501-507.
	B	Koji Nozaki et al., "A Novel Polymer for a 193-nm Resist," Journal of Photopolymer Science and Technology, Volumn 9, Number 3 (1996), pages 509-522.
	C	Robert D. Allen et al., "Single Layer Resits With enhanced Etch Resistance for 193 nm Lithography," Journal of Photopolymer Science and Technology, Volume 7, Number 3 (1994), pages 507-516.

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EXAMINER	DATE CONSIDERED
Judith M Olke	1/22/02

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